



Part of #1

Sheet 1 of 1

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U.S. Department of Commerce
Patent & Trademark OfficeAttorney Docket No.
2285/51302Serial No.
10/052,306**INFORMATION DISCLOSURE
STATEMENT**
(Use several sheets if necessary)

Applicant: Yumiko KAWANO, et al.

Filing Date
January 18, 2002

Group

U.S. PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub- Class	Filing Date (if appropriate)
	AA						
	AB						
	AC						
	AD						
	AE						
	AF						
	AG						
	AH						
	AI						

FOREIGN PATENT DOCUMENTS

Examiner Initial		Document Number	Date	Name	Class	Sub- Class	TRANSLATION	
							Yes	No
ER	AK	64-501	01/1989	Japan			No	
	AL	0349695	01/90	L'Air Liquide			No	
	AM	63-072881	04/88	Toshiba Corporation			Abstract	
	AN	09-186110	07/97	Tokyo Electron			Abstract	
	AO	05-078846	03/93	Osaka Gas Co.			Abstract	
	AP	05-226282	09/1993	NEC Corporation			Abstract	
ER	AQ	64-068474	09/1989	Tokyo Electron			Abstract	

OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, etc.)

CK	AR	S.C. SUN, et al. "Characterization of Diffusion Barrier Properties of CVD and PVD Tungsten Nitride Thin Films" VMIC Conference, June 18-20, 1996					
ER	AS	Toshiya SUZUKI, et al., "Comparison of CVD TiN, PECVD WN _x , and CVD W-Si-N as Upper Electrode Materials for Ta ₂ O ₅ DRAM Capacitors" Conference Proceedings ULSI XIII, 1998					
	AT						

EXAMINER

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12/11/02

EXAMINER: Initial if citation considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication.

